

PATENT ABSTRACTS OF JAPAN

(11)Publication number : **04-226461**

(43)Date of publication of application : **17.08.1992**

(51)Int.Cl.

G03F 7/039
G03F 7/004
G03F 7/004
G03F 7/029
G03F 7/26

(21)Application number : **03-081153**

(71)Applicant : **INTERNATL BUSINESS MACH
CORP <IBM>**

(22)Date of filing : **22.03.1991**

(72)Inventor : **ALLEN ROBERT D
WALLRAFF GREGORY M
SIMPSON LOGAN L
HINSBERG III WILLIAM D**

(30)Priority

Priority number : **90 513741** Priority date : **24.04.1990** Priority country : **US**

(54) LIQUID APPLICATION TYPE AQUEOUS-PROCESSABLE PHOTORESIST COMPOSITION

(57)Abstract:

PURPOSE: To obtain the photoresist having high sensitivity and high resolution by using a (tertiary-butyl methacrylate)/(methyl methacrylate)/(methacrylic acid) polymer binder and an initiator that generates an acid when it is exposed to radiation, as components of the composition.

CONSTITUTION: In this composition, the film-forming polymer binder used is an acrylic polymer that has acid-convertible side chains and is capable of forming a photoresist by allowing it to react with a selected luminescent agent through chemical-sensitizing reaction. Polymer chains of the polymer binder consist of a first monomer that provides a polymer main chain with the acid-sensitive side chain groups, a second monomer that is selected from alkyl methacrylates, alkyl acrylates and combinations of them, and a third monomer that is selected from acryl-based carboxylic acids and methacryl-based carboxylic acids.

LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]